



Substitute Form PTO-1449 (Modifed)		U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-034US1	Application No. 10/562,257
Information Disclosure Statement by Applicant (Use several sheets if necessary)		Applicant Shafer et al.		
(37 CFR 1.98(b))		Filing Date December 4, 2006	Group Art Unit 2621 2873	

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Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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	ATTT	Kawata et al., "Fabrication of 0.2mm Fine Patterns Using Optical Projection Lithography With an Oil Immersion Lens", Japanese Journal of Applied Physics, Japan Society of Applied Physics, Tokyo, Japan, vol. 31 no. 12B, Part 1, December 1, 1992, pp 4174-4177.
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<b>Other Documents (include Author, Title, Date, and Place of Publication)</b>		
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Examiner Signature <i>/William Choi/</i>	Date Considered 11/12/2007
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